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(54) **WASTE GAS TREATMENT APPARATUS FOR SEMICONDUCTOR AND DISPLAY PROCESSES**

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(57) **ABSTRACT**

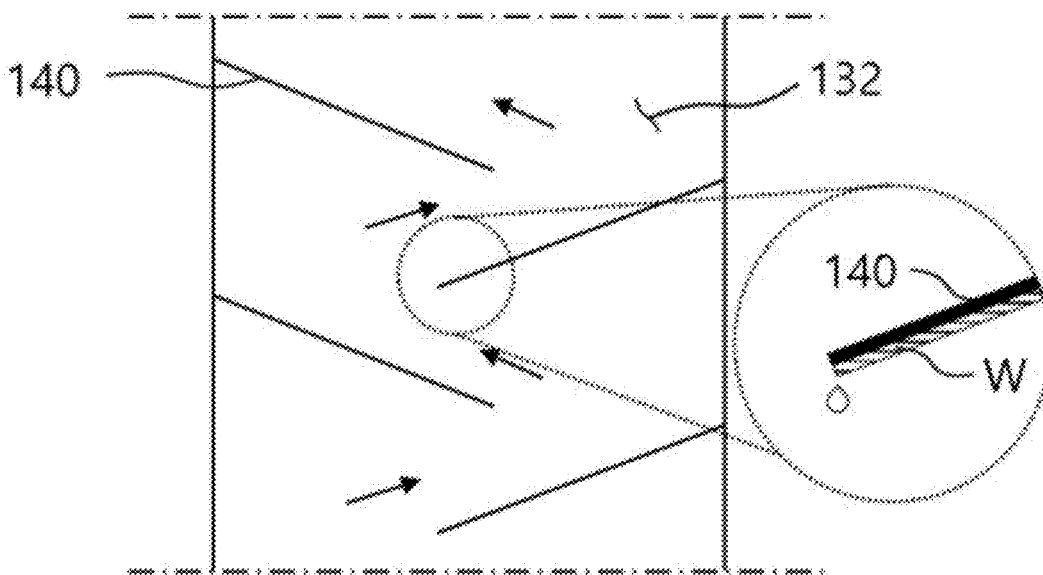
Disclosed is a waste gas treatment apparatus for semiconductor and display processes, the apparatus including: a pre-treatment unit having an inlet and an outlet formed therein, and configured to spray a cleaning solution to waste gas introduced through the inlet to primarily treat in the waste gas; a reaction unit configured to simultaneously treat fluorine compounds and nitrous oxide (N_2O) in waste gas discharged from the pre-treatment unit; a post-treatment unit configured to spray a cleaning solution to waste gas discharged from the reaction unit to secondarily treat in the waste gas; and a heat exchange unit installed between the pre-treatment unit and the reaction unit.

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→ **WASTE GAS FLOW DIRECTION**